EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1186	ohno-h$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:40
L2	1840	sekiguchi-k	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:41
L3	4572	sekiguchi-k$.in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:41
L4	5736	l1 or l3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:41
L5	255310	(clean or cleaning or cleaned or cleanse or cleansed or cleansing or cleanser or wash or washing or washed or rinse or rinsing or rinsed or treat or treated or treatment or treating) with (semiconductor or wafer or silicon)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:43
L6	466	(nozzle or jet or jetted) with (move or moving or moved or transvers$4) with (center or radial or radially) with (peripher$ or edge or end adj3 face) same (gas or nitrogen or "N2" or "N.sub.2" or inert adj gas)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 16:59

L7	2	"20060048792".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 17:00
L8	2	"5882433".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 17:01
L9	2	"20040074526".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 17:04
L10	2	"20030192577".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 19:43
L11	2	"20060042722".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 19:48
L12	2	"5997653".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 19:49
L13	2	"6589359".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 19:50
L14	2	"6770151".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 19:54

L15	1338315	(clean or cleaning or cleaned or cleanse or cleansed or cleansing or cleanser or wash or washing or washed or rinse or rinsing or rinsed or treat or treated or treatment or treating or dry or drying or dried or process or processing or processed) with (semiconductor or wafer or silicon or substrate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 20:18
L16	660	(nozzle or jet or jetted or spray or spraying or sprayed or jetting) with (move or moving or moved or transvers$4) with (center or radial or radially or central or middle) with (peripher$ or edge or end adj3 face) same (gas or nitrogen or "N2" or "N.sub.2" or inert adj gas or inactive adj3 gas or surface adj3 tension)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 20:19
L17	301864	("134"/$ or "438"/$).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 20:19
L18	174	l15 and l16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 20:24
L19	86	l18 and l17	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/01/25 20:24
L20	0	("2008/0251101").URPN.	USPAT	OR	ON	2010/01/25 20:37
L21	0	("2008/0251101").URPN.	USPAT	OR	ON	2010/01/25 20:37
L22	0	("2008/0251101").URPN.	USPAT	OR	ON	2010/01/25 20:37
L23	0	("2007/0246079").URPN.	USPAT	OR	ON	2010/01/25 22:30

L24	0	"20030079764".pn.	USPAT	OR	ON	2010/01/25 22:51
L25	1	"20030079764".pn.	US-PGPUB; USPAT	OR	ON	2010/01/25 22:51
L26	1	"20040040177".pn.	US-PGPUB; USPAT	OR	ON	2010/01/25 22:55

EAST Search History (Interference)

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1/25/2010 11:02:37 PM